

Form PTO-1449 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 119364	APPLICATION NO. New U.S. Patent Application	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANTS Etienne QUESNEL et al. FILING DATE April 5, 2004		
U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
/RM/	1	4,392,453	7/12/1983	LUSCHER		
FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS
/RM/	2	JP A 7-291790 w/ Abst & Trans	11/7/1995	Japan		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)						
/RM/	3	KOJIMA et al. "IMPURITY GENERATION FOR LOW ENERGY RANGE OF ION BOMBARDMENT AND ITS TRANSPORT IN A PLASMA," Journal of Nuclear Materials 241-243 (1997), pp. 1248-1252.				
/RM/	4	WALTON et al. "EXTREME ULTRAVIOLET LITHOGRAPHY - REFLECTIVE MASK TECHNOLOGY," Emerging Lithographic Technologies IV, Proceedings of SPIE Vol. 3997 (2000) pp. 496-507.				
/RM/	5	HUE et al. "REDUCTION OF DEFECT DENSITY ON BLANKS: APPLICATION TO THE EXTREME ULTRAVIOLET LITHOGRAPHY," Microelectric Engineering 61-62 (2002), pp. 203-211.				
EXAMINER: /Rodney McDonald/				DATE CONSIDERED 03/26/2007		
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						

Date: April 5, 2004